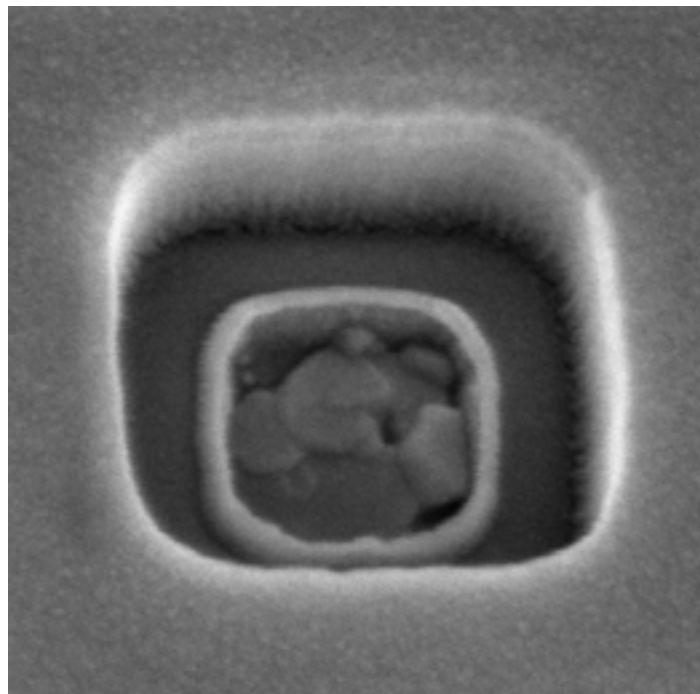


## Aqueous-Based Post-Ash Cleaner



Covidien's Mallinckrodt Baker specialty chemicals business is launching a powerful new solution to improve post-ash residue removal processes for semiconductor manufacturing. The BAKER CLK™ -168 post-ash cleaner is the latest in the Company's complete line of semiconductor chemicals designed for today's difficult process integration challenges. The post-ash residue remover is specifically formulated to provide maximum compatibility with low-k dielectrics, copper, advanced barrier layers and etch-stop materials. The aqueous-based cleaner:

- Effectively removes etch / ash residues and sidewall polymers.
- Offers short operating times of 15 to 90 seconds for a single wafer process.
- Has low operating temperatures starting at 25 °C.
- Is designed for use in bath, batch spray and single wafer tools.
- Provides long bath life — typically greater than 48 hours.

[www.mallbaker.com/micro](http://www.mallbaker.com/micro) [1]

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### Links:

[1] <http://www.chem.info/WorkArea/www.mallbaker.com/micro>

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